

# EECS251B : Advanced Digital Circuits and Systems

## Lecture 23 – Optimal Thresholds

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### Broadcom launches Wi-Fi 7 chips

April 13, 2022 [Nitin Dahad](#)

Broadcom's new family of Wi-Fi 7 chips will help implement the speed, latency and determinism, and features like multi-link operation offered by the new Wi-Fi standard.



Broadcom's new Wi-Fi 7 product family. (Image: Broadcom)

# Recap

- Limiting transistor leakage
  - Multi-threshold designs
  - Transistor stacking
  - Sleep modes
  - Power gating

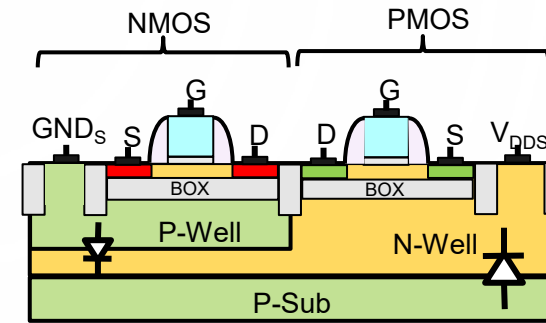
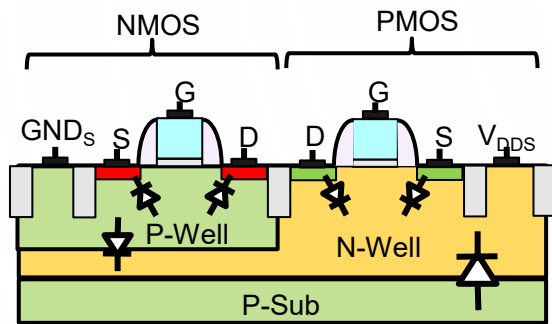


## Dynamic Threshold Scaling

# Dynamic Body Bias

- Similar concept to dynamic voltage scaling
- Control loop adjusts the substrate bias to meet the timing/leakage goal
  - Can be used just as runtime/sleep
- Limited range of threshold adjustments in bulk ( $<100\text{mV}$ )
  - Limited leakage reduction ( $<10\times$ )
- Works well in FDSOI ( $80\text{-}85\text{mV/V}$ , with  $\sim 1.8\text{V}$  range)
- No delay penalty
  - Can increase speed by forward bias
- Energy cost of charging/discharging the substrate capacitance
  - but doesn't need a regulator

# FDSOI and Bulk



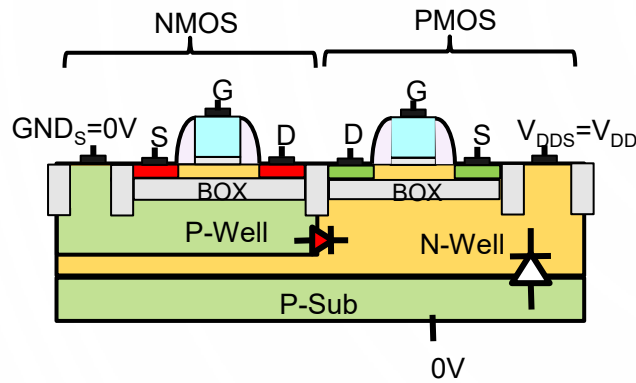
## • Bulk CMOS

- Leakage paths through bulk
- RDF dominates local variability
- Diodes and B2B tunneling limit back-bias range

## ► UTBB FD-SOI

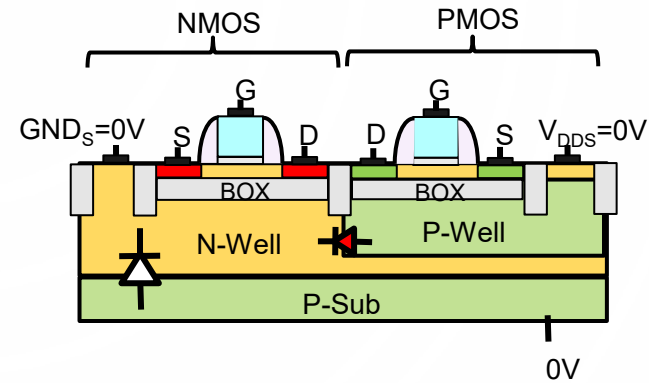
- Thin body for short-channel control
- No doping – less RDF
- Extended back-bias range

# FDSOI Wells and Back Bias



## ► Typical (RVT)

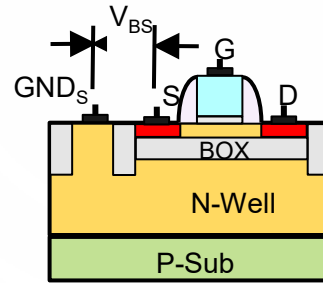
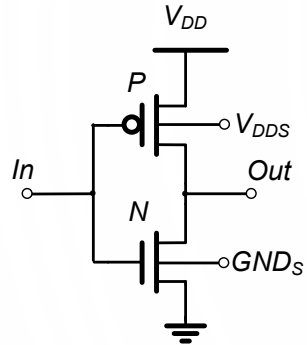
- $GND_{S, \text{nom}} = 0V, V_{DDS, \text{nom}} = V_{DD}$
- Reverse body bias,  $V_{BSN} < 0V$
- $(-3V) < GND_S < V_{DD}/2 + 0.3V$ 
  - Limit due to diodes, BOX
- Can reverse bias 2-3V each



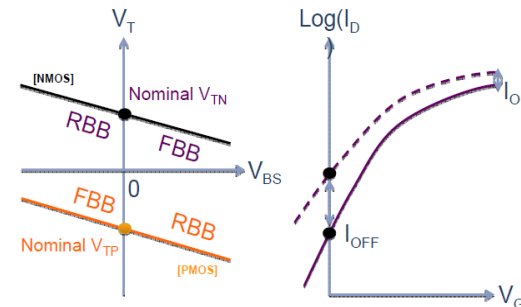
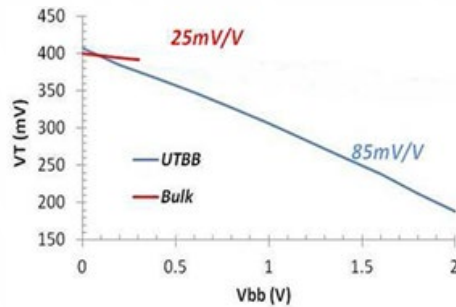
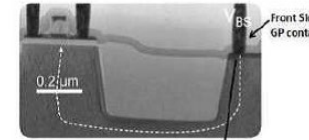
## • Flip-well (LVT)

- $V_{DDS, \text{nom}} = GND_{S, \text{nom}} = 0V$
- Forward body bias  $V_{BSN} > 0V$
- $0.3V < GND_S < (3V)$ 
  - Limit due to diodes, BOX
- Can forward bias 2-3V each

# Back-Bias in FDSOI

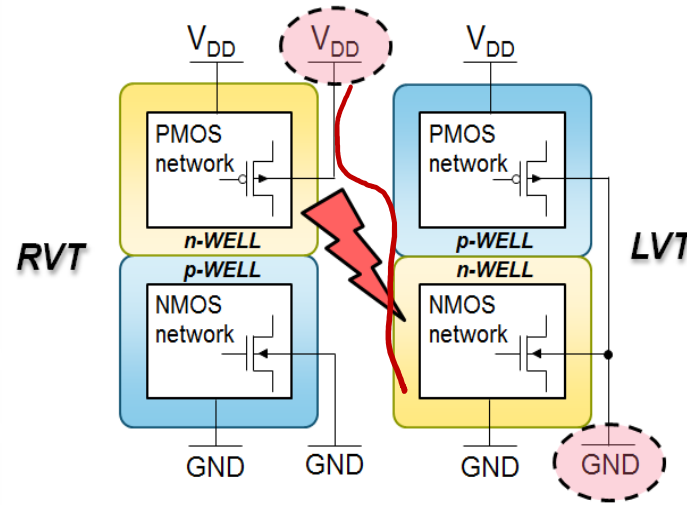


Back-gate contact



- $\gamma = 85mV/V$  body coefficient, and extended voltage range
- Lower coefficient and voltage range in bulk, finFET

# Multi $V_{Th}$



- No channel implant in 28FDSOI
  - No multi  $V_{Th}$
- Can't abut wells
  - RVT and LVT require different well biases



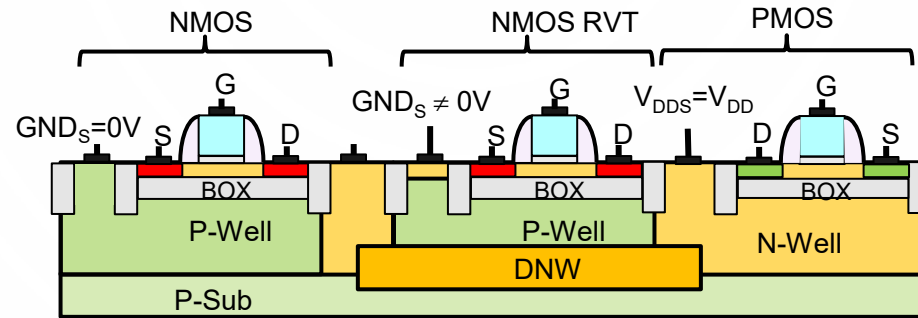
# Back Bias in FDSOI

The diagram illustrates the cross-sectional structure of three FDSOI devices: NMOS, NMOS RVT, and PMOS. The NMOS and NMOS RVT devices are built on a P-Well, while the PMOS device is built on an N-Well. All devices share a common P-Substrate. The NMOS RVT device features a Deep N-Well (DNW) layer beneath the P-Well. The gate stack consists of a Gate (G), a BOX layer, and a P-Well layer. The source (S) and drain (D) regions are shown. The NMOS RVT device is biased with  $GND_S \neq 0V$ , while the NMOS and PMOS devices are biased with  $GND_S = 0V$  and  $V_{DDS} = V_{DD}$  respectively.

- Triple well (deep N-Well, DNW) allows for separate back bias
- Layout penalty; capacitance to drive

EECS251B L22 OPTIMAL THRESHOLDS

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- Triple well (deep N-Well, DNW) allows for separate back bias
- Layout penalty; capacitance to drive

# Digital Logic: UPF

- Supply, back-bias defined in Unified Power Format (UPF)
  - Or Common Power Format (CPF)
- Handled by synthesis, place and route tools

UPF description of PT\_TOP with GND, VDD, GNDS and VDDS supplies.

```
create_power_domain PD_TOP
```

```
create_supply_port GND
```

```
create_supply_port VDD
```

```
create_supply_net GND -domain PD_TOP
```

```
connect_supply_net GND -ports {GND}
```

```
create_supply_net VDD -domain PD_TOP
```

```
connect_supply_net VDD -ports {VDD}
```

```
set_domain_supply_net PD_TOP -primary_power_net VDD -primary_ground_net GND
```

```
# Body-bias specification
```

```
create_supply_port VDDS
```

```
create_supply_port GNDS
```

```
create_supply_net VDDS -domain PD_TOP
```

```
connect_supply_net VDDS -ports {VDDS vddgndvdds*/VDDSCORE}
```

```
create_supply_net GNDS -domain PD_TOP
```

```
connect_supply_net GNDS -ports {GNDS gnds*/VDDCORE1V8}
```

```
create_supply_set back_bias_set \
```

```
-function {nwell VDDS} \
```

```
-function {pwell GNDS} \
```

```
-reference_gnd {GND} \
```

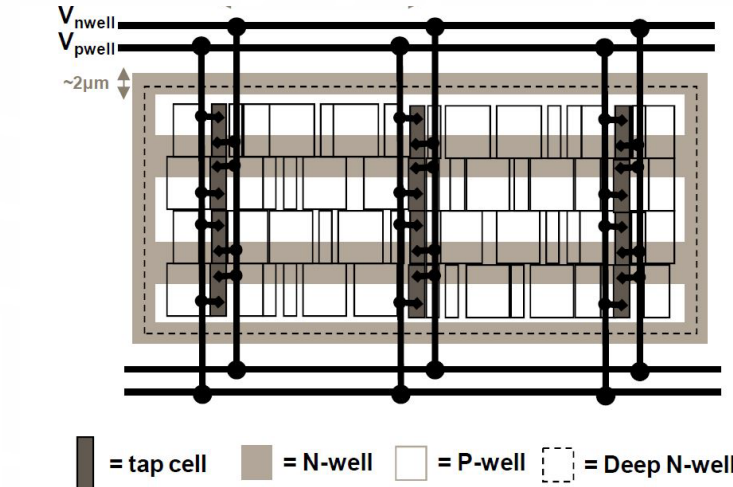
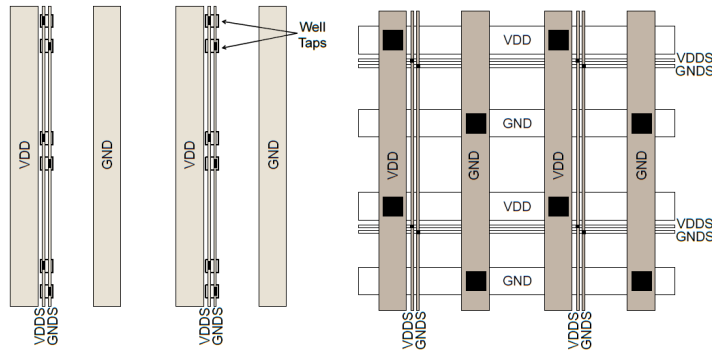
```
create_power_domain PD_TOP -update -supply bias
```

```
associate_supply_set back_bias_set -handle PD_TOP.bias
```

M.Blagojevic, Ph.D. Dissertation, ISEP 2017

# Digital Logic - Implementation

- Well taps added explicitly
  - Difference from bulk

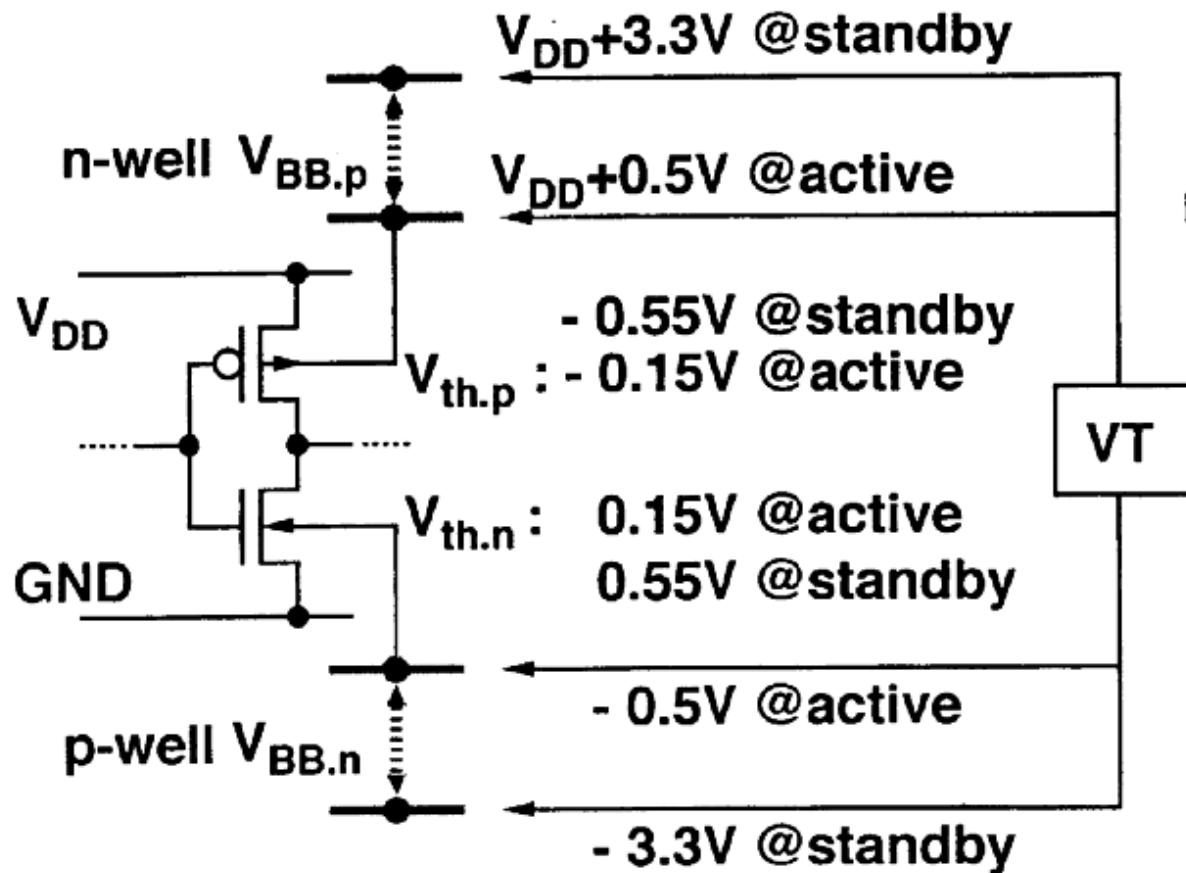


## Back bias straps

- Low DC current
- Except for very fast transitions

# Dynamic Body Bias (Bulk)

ISSCC'96 pp.166-167



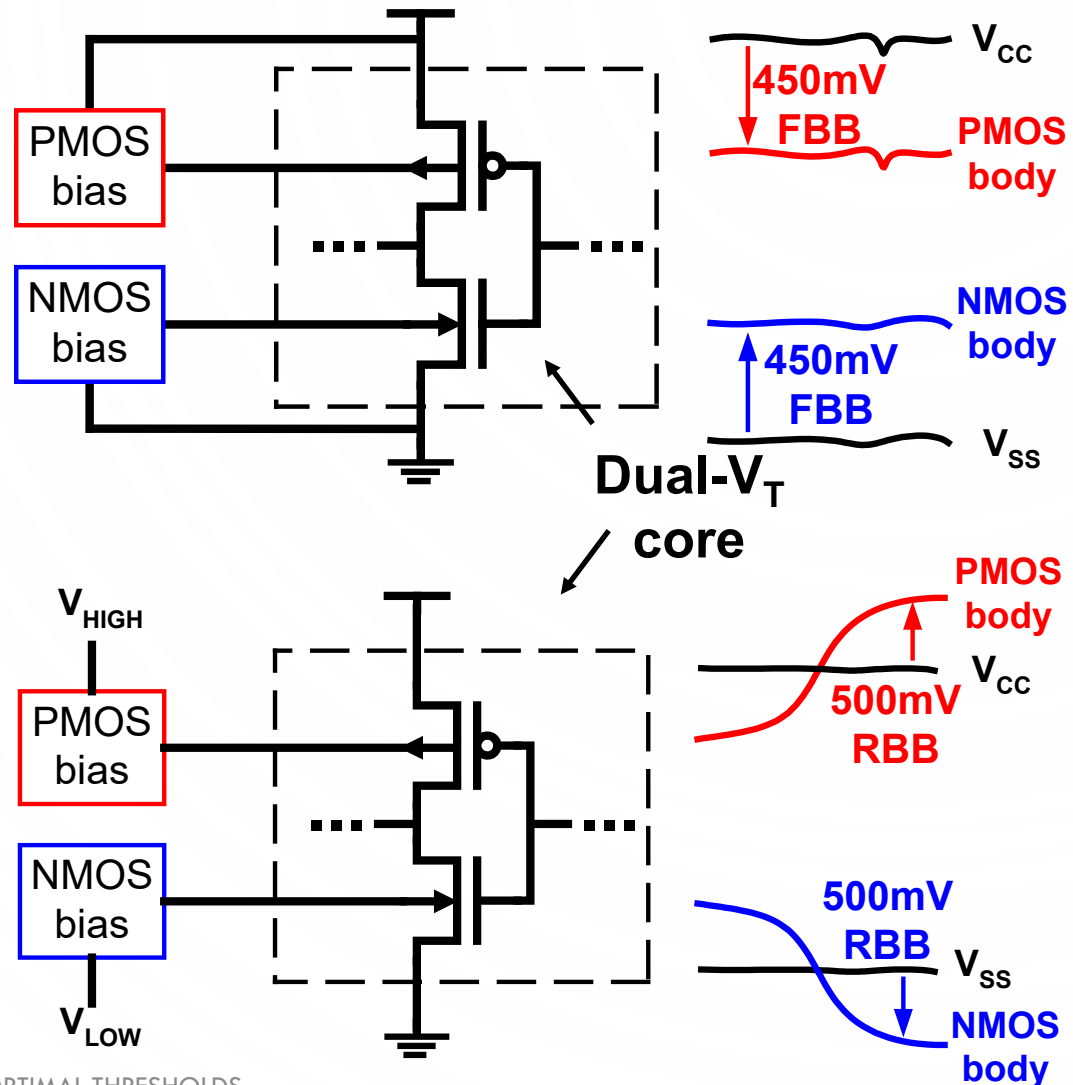
VTCMOS :

Dynamic  $V_{th}$  control for  
low power through  
backgate bias

example:

(SATS) or (SPR) or  
(SATS + SPR)

# Dynamic Body Bias (Bulk)



## Active mode

Forward body bias  
(FBB)

Local  $V_{CC}$  tracking

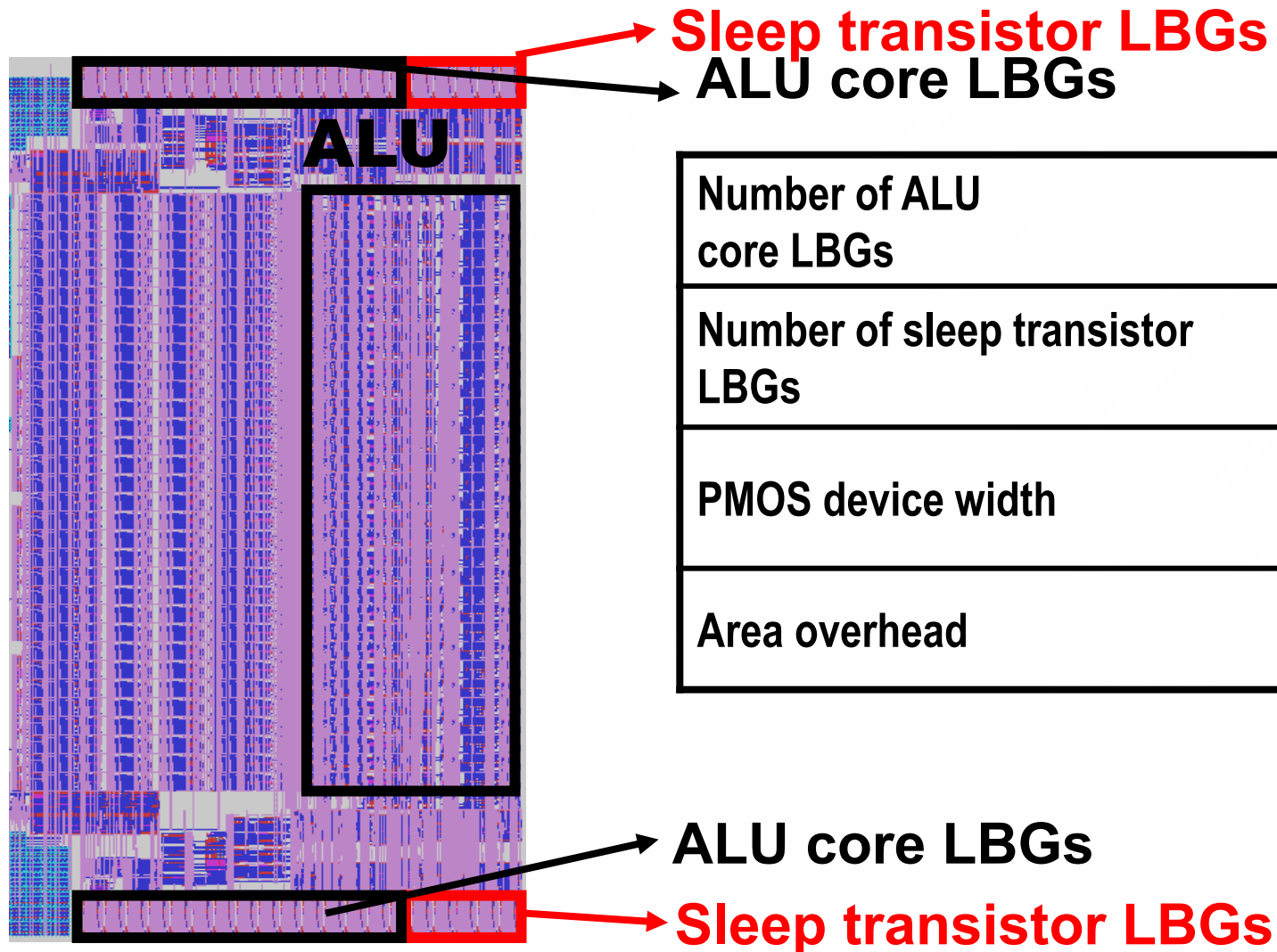
## Idle mode

Reverse body bias  
(RBB)

Triple well needed

Tschanz, ISSCC'03

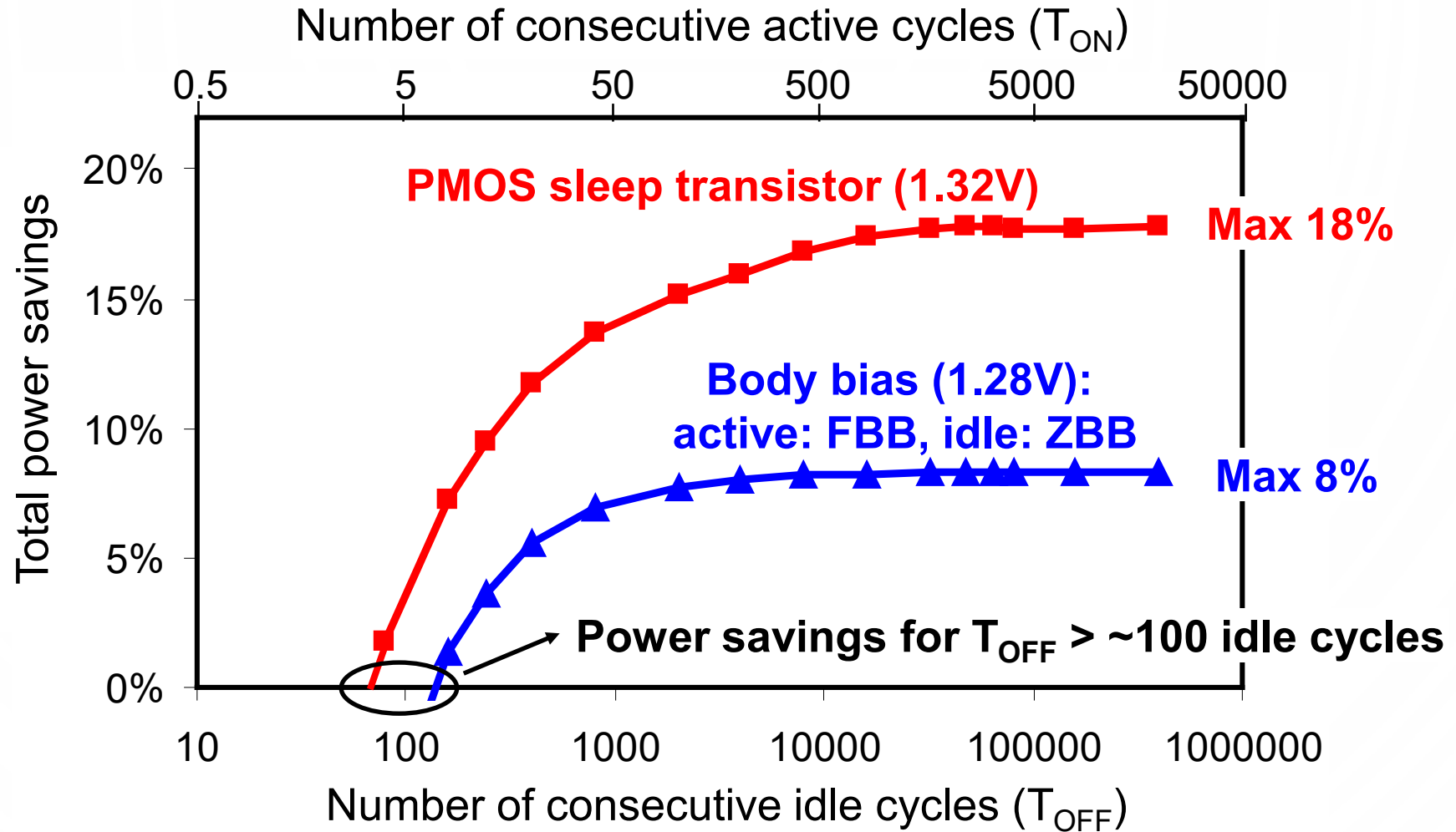
# Body Bias Layout



Number of ALU core LBGs	30
Number of sleep transistor LBGs	10
PMOS device width	13mm
Area overhead	8%

# Total Active Power Savings

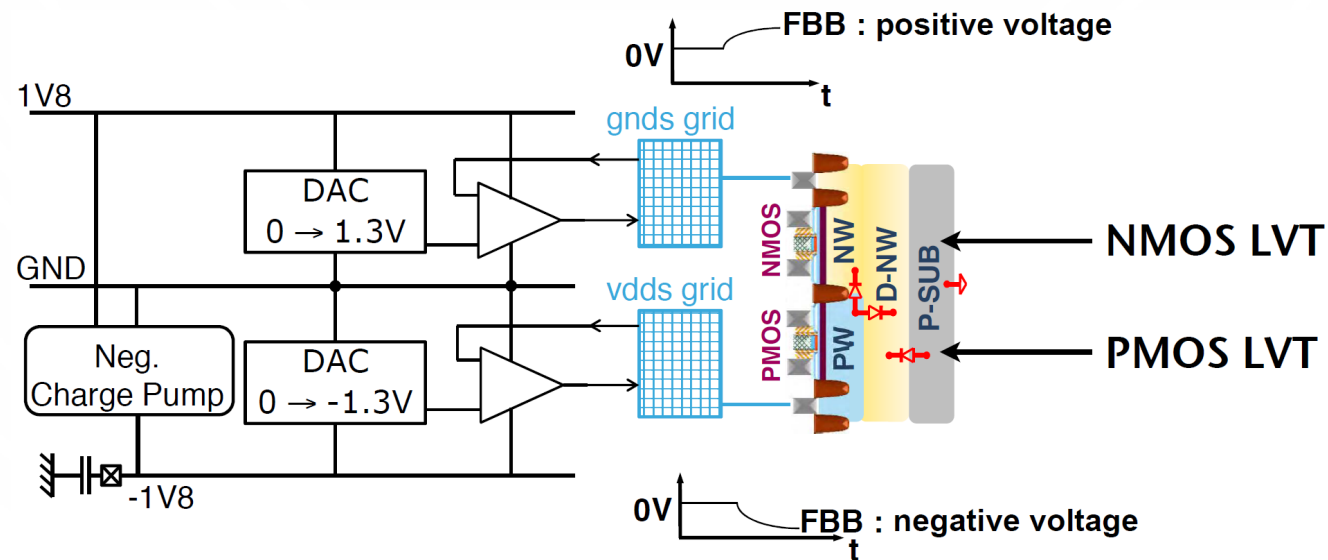
(Fixed activity:  $\alpha = 0.05$ )



**Reference: 450mV FBB to core with clock gating, 1.28V, 4.05GHz, 75°C**

# Generating Back-Bias

- Tradeoff – speed of charging and discharging well caps
- Often measure  $V_{BB}$  indirectly (leakage)
- Challenge: Generating  $-V_{SS}$
- 28nm FDSOI implementation

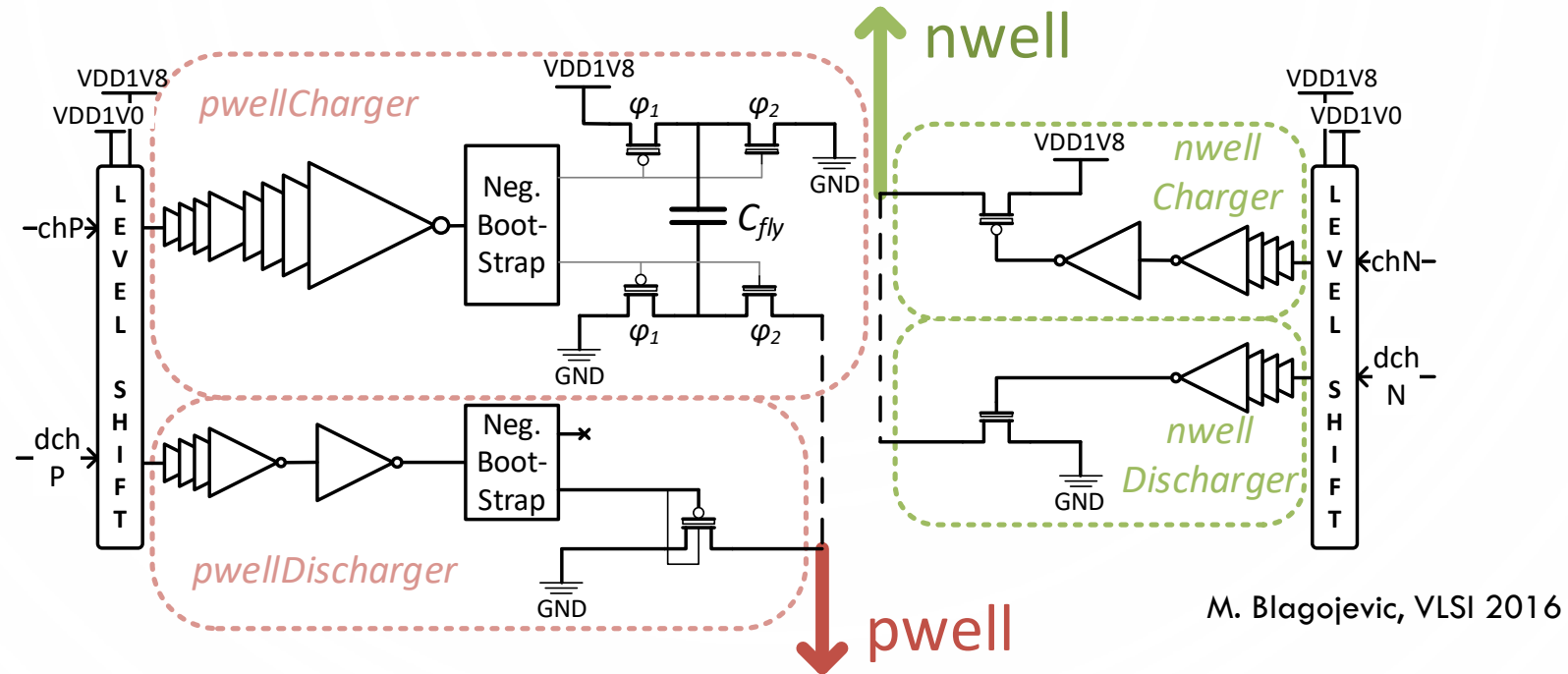


D. Jacquet, VLSI 2013



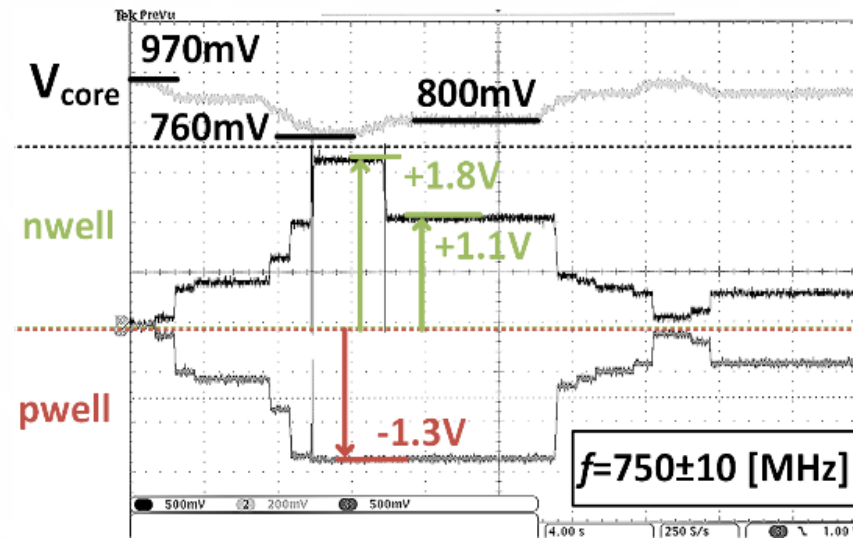
# Generating Back Bias

- Fast and wide voltage range back-bias in FDSOI



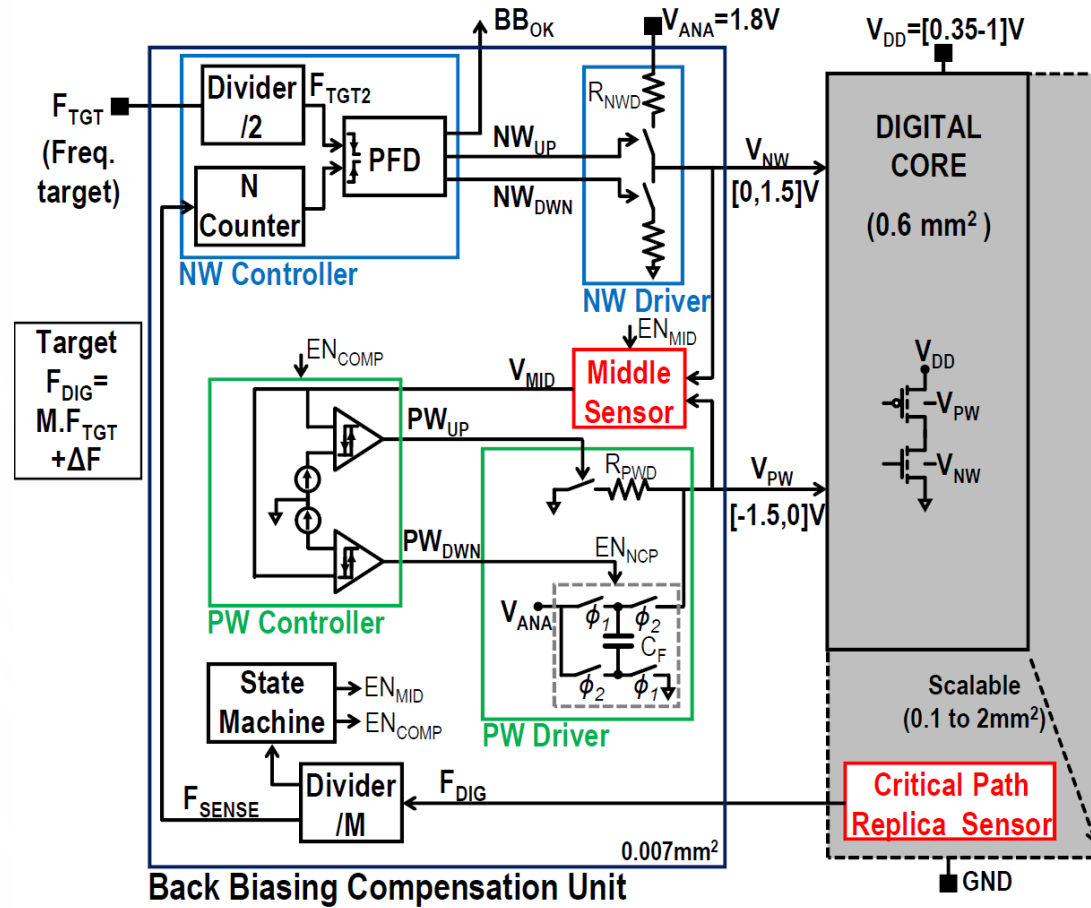
Switched capacitors generate negative bias and pump substrate

# Supply/Process Compensation



- Able to track  $\sim 200\text{mV}$  supply droops and maintain constant frequency (measured by a replica) by back-bias adjustments

# Dynamic Frequency Loop in FDSOI



Quelen, ISSCC'18

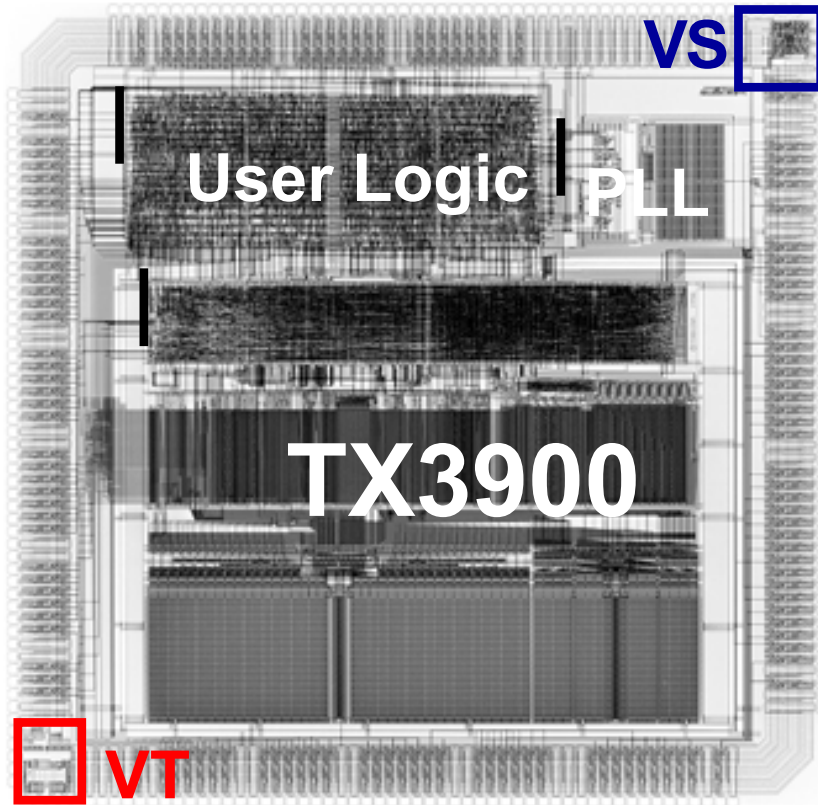
# Announcements

- Quiz 3 today
- Homework 4 due next week

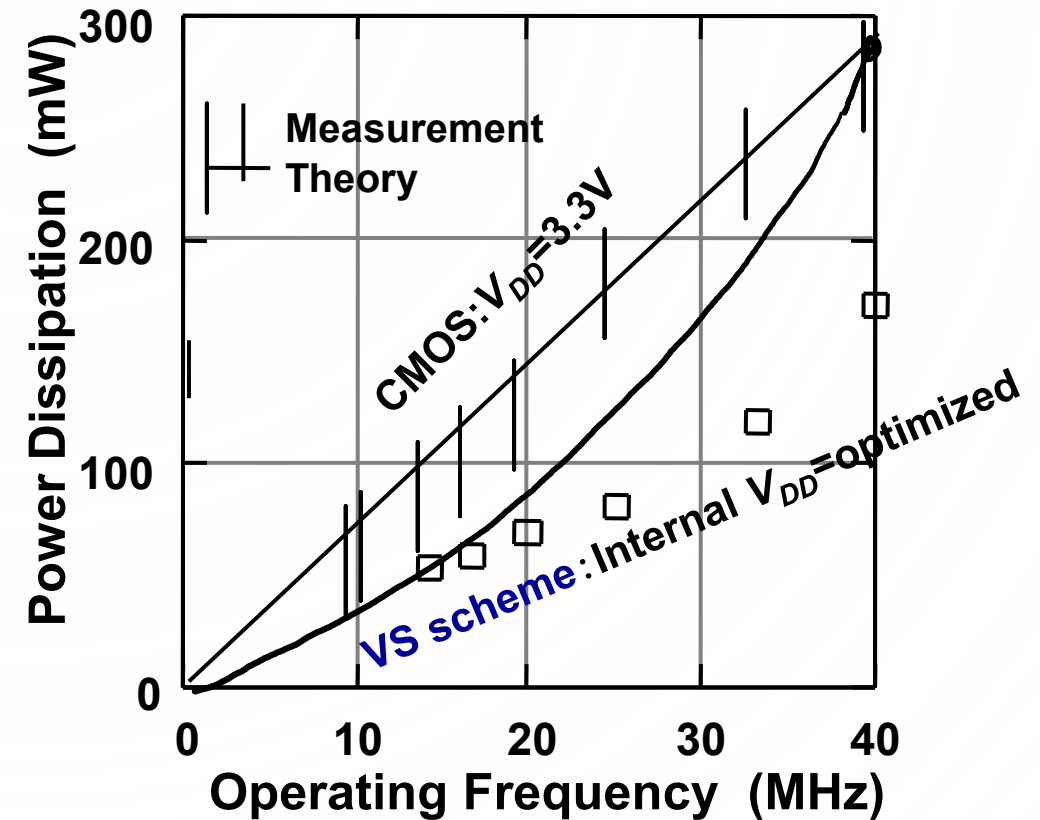


## 5.0 Optimal $V_{DD}$ , $V_{Th}$

# Dynamic Voltage Scaled Microprocessor

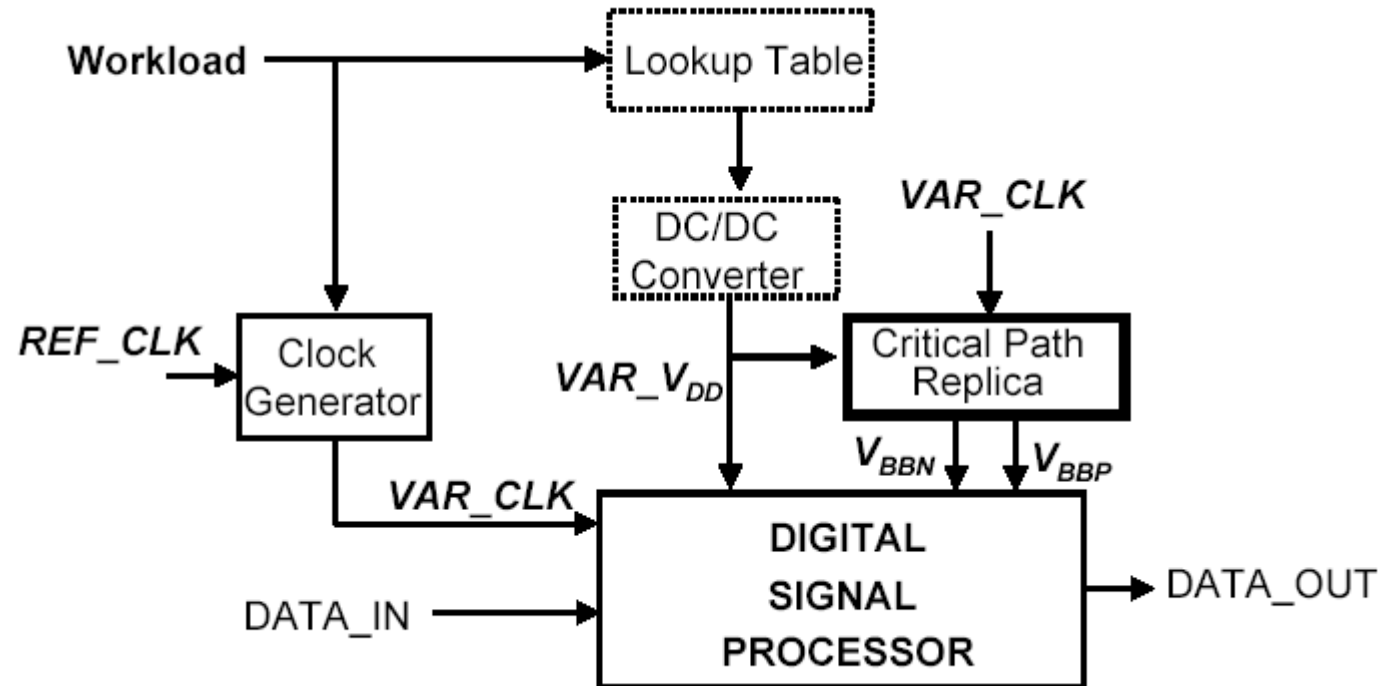


External  $V_{DD}$   $3.3V \pm 10\%$   
Internal  $V_{DDL}$   $0.8V \sim 2.9V \pm 5\%$



Courtesy: Prof. Kuroda

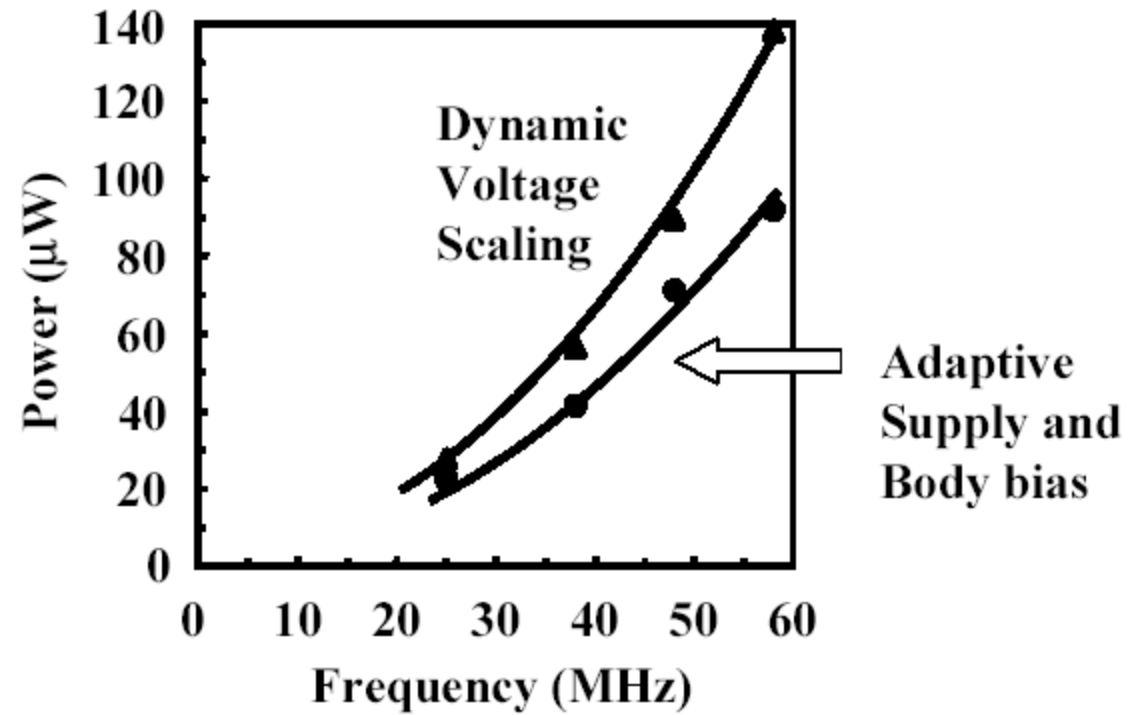
# Adapting $V_{DD}$ and $V_{TH}$



- Adapting both  $V_{DD}$  and  $V_{Th}$  during runtime
  - $V_{Th}$  is much less sensitive

Miyazaki, ISSCC'02

# Adapting $V_{DD}$ and $V_{TH}$



Miyazaki, ISSCC'02

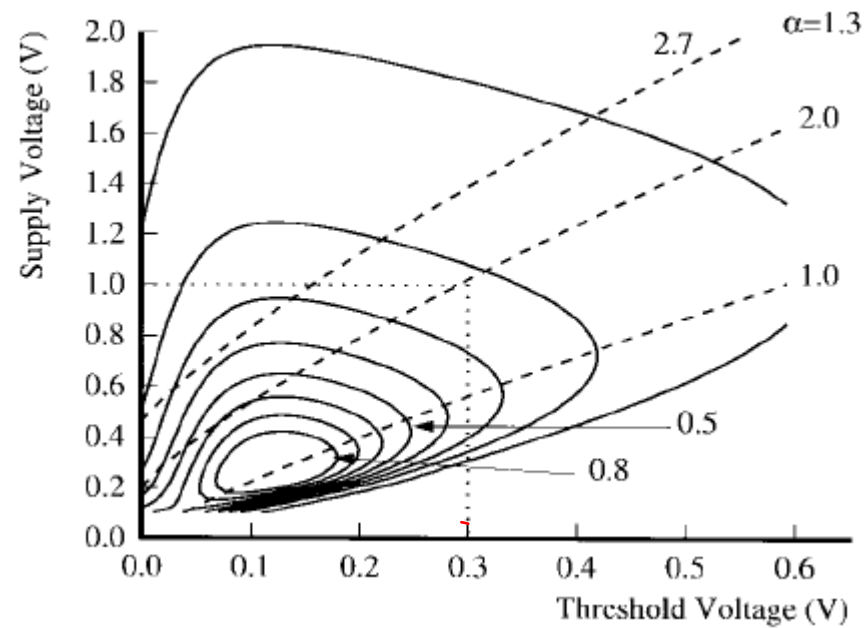


## Optimal $V_{DD}$ , $V_{Th}$

- Adjusting  $V_{DD}$ ,  $V_{Th}$  trades of energy and delay
- We studied energy-limited design
  - And alternate ways for optimizing energy and delay together
  - E.g. energy-delay product (EDP)
  - Or  $E^n D^m, n, m > 1$

# Optimal EDP Contours

- Plot of EDP curves in  $V_{DD}$ ,  $V_{Th}$  plane



Gonzalez, JSSC 8/97

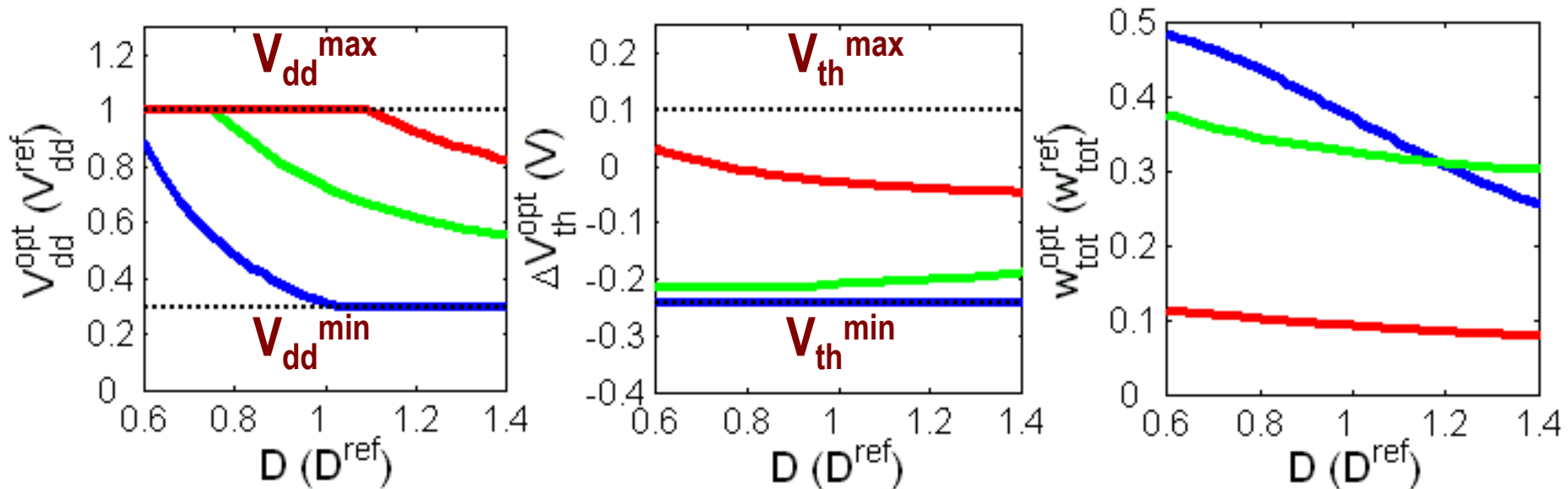
# Sizing, Supply, Threshold Optimization

Reference Design:

$D^{\text{ref}} (V_{\text{dd}}^{\text{max}}, V_{\text{th}}^{\text{ref}})$

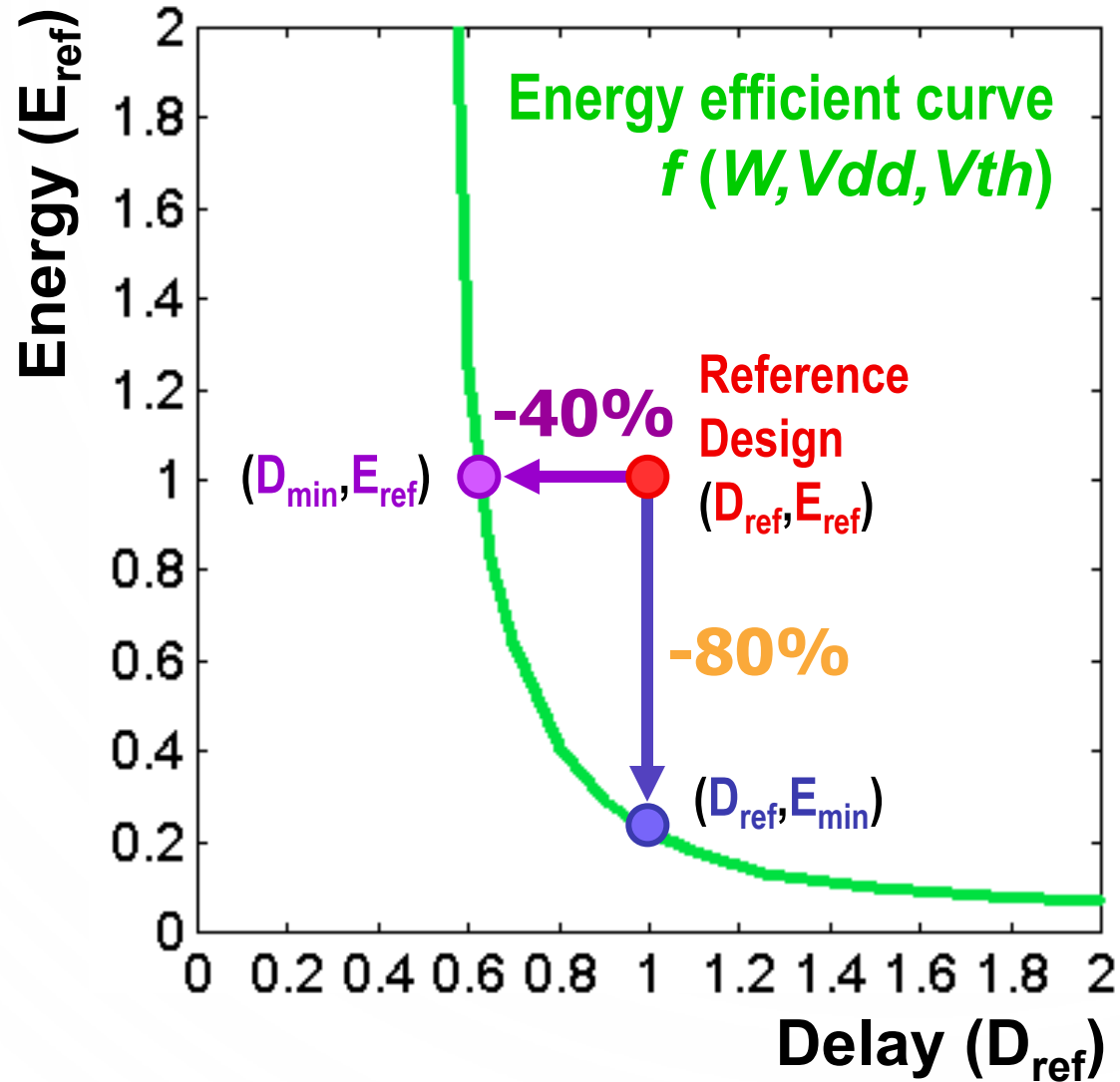
Topology	Inverter	Adder	Decoder
$(E_{Lk}/E_{Sw})^{\text{ref}}$	0.1%	1%	10%

Large variation in optimal circuit parameters  $V_{\text{dd}}^{\text{opt}}, V_{\text{th}}^{\text{opt}}, w^{\text{opt}}$



**Technology parameters ( $V_{\text{dd}}^{\text{max}}, V_{\text{th}}^{\text{ref}}$ ) rarely optimal**

# Result: E-D Tradeoff in an Adder



Sensitivity	W	Vdd	Vth
$(D_{ref}, E_{ref})$	$\infty$	1.5	0.2
$(D_{ref}, E_{min})$	1		
$(D_{min}, E_{ref})$	22	16	22

**80% of energy saved  
without delay penalty**

**40% delay improvement  
without energy penalty**

# Energy-constrained delay

- Active power

$$P_{act} = \alpha f C V_{DD}^2$$

$$f = 1 / L_D t_p$$

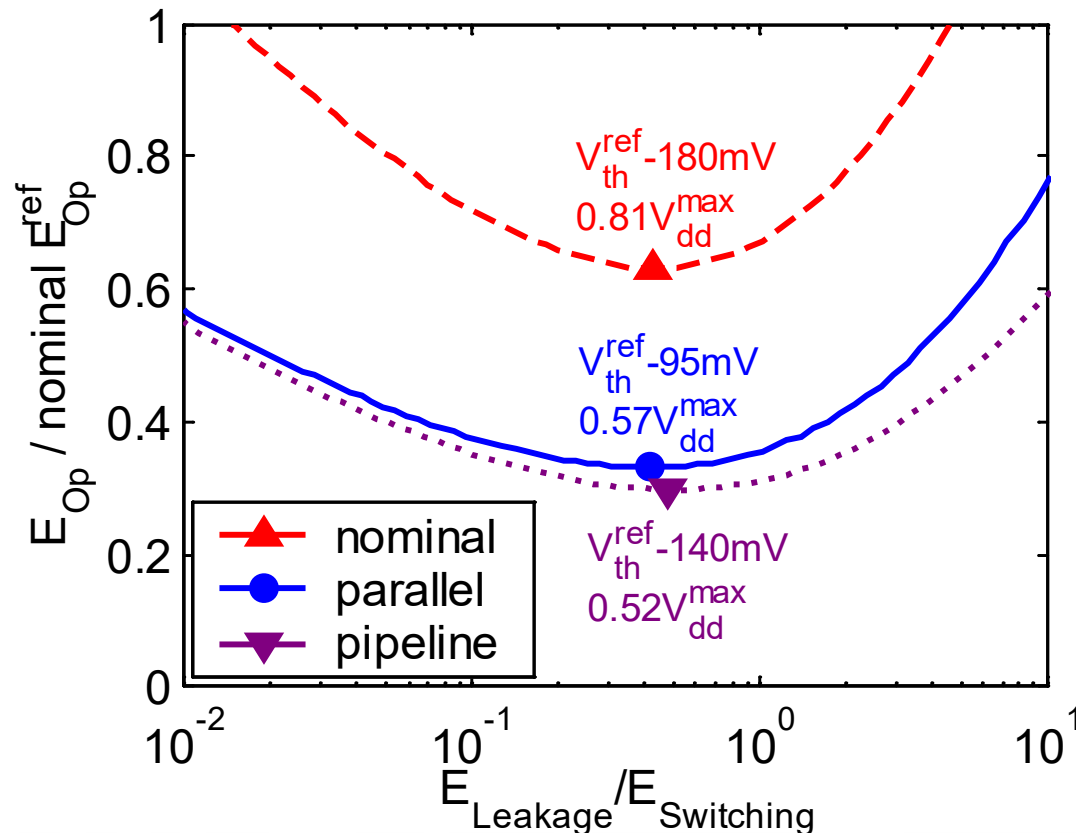
- Leakage power

$$P_{leak} = I_0 e^{\frac{-V_{Th} - \gamma V_{DD}}{S}} V_{DD}$$

- Eliminate one variable( $V_{Th}$ ) and find  $P_{min}(V_{DD})$

Nose, ASP-DAC'00

Minimum energy:  $E_{Sw} = 2E_{Lk}$

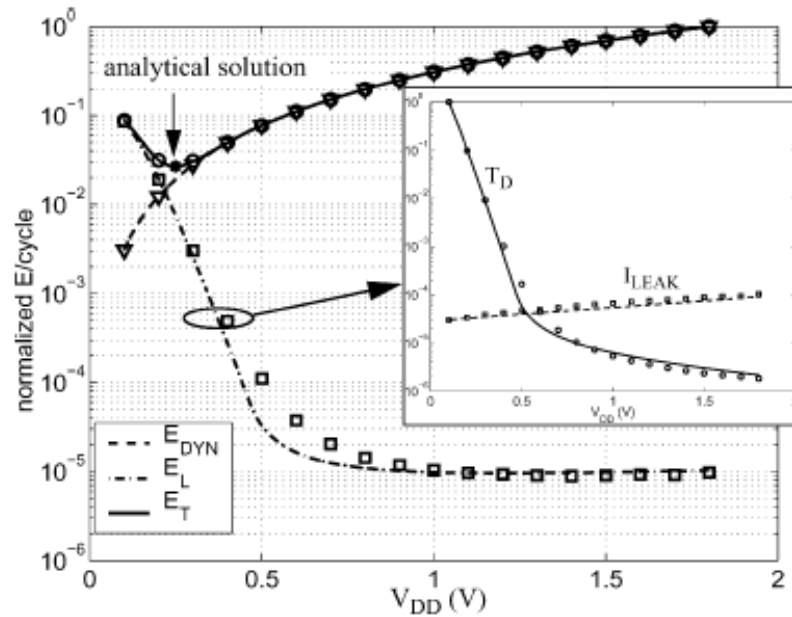


- ◆ Large  $(E_{Lk}/E_{Sw})^{opt}$
- ◆ Flat  $E_{Op}$  minimum
- ◆ Topology dependent

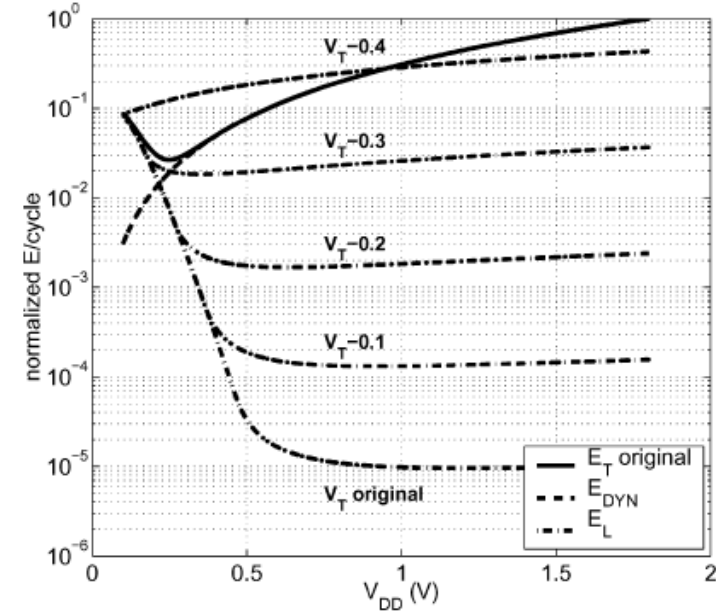
$$(E_{Lk}/E_{Sw})_{opt} = \frac{2}{\ln\left(\frac{L_d}{\alpha_{avg}}\right) - K}$$

**Optimal designs have high leakage ( $E_{Lk}/E_{Sw} \approx 0.5$ )**

# Subthreshold Optimum



$f = 30\text{kHz}$



Minimum is independent of  $V_T$

Calhoun, JSSC 9/05

# Summary

- Body effect weak in bulk CMOS
  - Strong in FDSOI
- Dynamic threshold scaling
  - Primarily for leakage control, process compensation
- Optimal thresholds
  - Total energy is minimized with 1/3 being leakage



## Next Lecture

- Clock generation and distribution